

IN THE CLAIMS:

1. (Currently Amended) A vacuum processing apparatus for applying a predetermined process to an object to be processed which is placed on a substantially circular placement stage provided in a vacuum chamber by supplying a process gas to the vacuum chamber, wherein:

said vacuum chamber has a substantially circular exhaust port under said placement stage, the exhaust port having a diameter equal to or smaller than a diameter of said placement stage;

a center axis of said exhaust port is displaced from a center axis of said placement stage; and

a foot-print of said placement stage covers ~~a portion~~ less than a whole surface of said exhaust port.

2. (Previously Presented) The vacuum processing apparatus as claimed in claim 1, wherein:

a support part is provided to support said placement stage by extending from a side wall of said vacuum chamber toward a center of said vacuum chamber; and

a direction of displacement of the center axis of said exhaust port with respect to the center axis of said placement stage is a direction opposite to an extending direction of said support part.

3. (Previously Presented) The vacuum processing apparatus as claimed in claim 2, wherein said support part has a hollow structure, and a utility supply line is provided therein.

4. (Previously Presented) The vacuum processing apparatus as claimed in claim 3, wherein said utility supply line includes at least one of a gas supply line, a cooling medium supply line and a power supply line.

5. (Previously Presented) The vacuum processing apparatus as claimed in claim 3, wherein said support part is detachably attached to said vacuum chamber.

6. (Previously Presented) The vacuum processing apparatus as claimed in one of claims 1 to 5, wherein a baffle plate is provided to surround said placement stage.
7. (Previously Presented) The vacuum processing apparatus as claimed in claim 6, wherein said baffle plate has a plurality of apertures, and an open area ratio on a side to which said exhaust port is displaced is smaller than an open area ratio on an opposite side to which said exhaust port is displaced.
8. (Previously Presented) The vacuum processing apparatus as claimed in one of claims 1 to 5, wherein a displacement of the center axis of said exhaust port with respect to the center axis of said placement stage is equal to or smaller than one eleventh of a diameter of said exhaust port.
9. (Previously Presented) The vacuum processing apparatus as claimed in one of claims 1 to 5, wherein said exhaust port is connected to a vacuum pump having a capacity to maintain said vacuum chamber at a pressure less than 10 Pa.
10. (Previously Presented) The vacuum processing apparatus as claimed in claim 9, wherein said vacuum pump is a turbo-molecular pump.
11. (Previously Presented) The vacuum processing apparatus as claimed in one of claims 1 to 5, wherein a gas supply part constituting a substantially circular showerhead is provided in said vacuum chamber, and a center axis of said showerhead is coincident with the center axis of said placement stage.
12. (Previously Presented) The vacuum processing apparatus as claimed in claim 11, wherein said placement stage and said gas supply part are configured to supply a film deposition process to said object to be processed.
13. (Previously Presented) The vacuum processing apparatus as claimed in one of claims 1 to 5, wherein an upper electrode and a lower electrode are provided facing each other, and

plasma of a process gas is generated between said upper electrode and said lower electrode to apply a film deposition process to said object to be processed by the generated plasma.

14. – 15. (Canceled)